

FORM PTO-1449 (MODIFIED) LIST OF PATENTS AND PUBLICATIONS FOR APPLICANTS INFORMATION DISCLOSURE STATEMENT	ATTORNEY DOCKET NO. Berkey 48-8-2A	SERIAL NO. To Be Assigned
	APPLICANT Berkey et al.	
	FILING DATE Herewith	GROUP: 1756

1903 U.S. PTO
 09/876394
 06/06/01

REFERENCE DESIGNATION				U.S. PATENT DOCUMENTS			
Examiner Initial		Document Number	Date	Name	Class	Sub-Class	Filing Date if Approp.
JL	AA1	5,698,484	12/16/97	Maxon	501	54	
	AB1	5,702,495	12/30/97	Hiraiwa et al.	65	17.1	
	AC1	5,702,847	12/30/97	Tarumoto et al.	430	5	
	AD1	5,707,908	1/13/98	Komine et al.	501	53	
	AE1	5,735,921	4/7/98	Araujo et al.	65	32.1	
	AF1	5,764,345	6/9/98	Fladd et al.	356	35.5	
	AG1	5,837,024	11/17/98	Fabian	65	17.4	
JL	AK1	5,970,746	10/26/99	Fujinoki et al.	65	102	

FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Sub-Class	Translation	
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JL	AA	98/27018	6/25/98	PCT	C03B	19/14	X	
	AB	98/52879	11/26/98	PCT	C03B	19/14	X	
	AC	0 401 845 A2	12/12/90	EPO	G02B	1/00	X	
	AD	0 483 752 A2	5/6/92	EPO	C03C	3/06	X	
	AE	0 488 320 A1	6/3/92	EPO	C03C	3/06	X	
	AF	0 607 433 B1	11/4/98	EPO	C03B	23/06	X	
	AG	0 636 586 A1	2/1/95	EPO	C03C	3/06	X	
	AH	0 870 737 A1	10/14/98	EPO	C03C	3/06	X	
	AI	0 901 989 A1	3/17/99	EPO	C03B	19/14	X	
	AJ	2,184,434	6/24/87	United Kingdom	C03B	20/00	X	
	AK	2,704,015 A1	8/3/78	Germany	C03B	23/04	X	
	AL	63-210044	8/31/88	Japan	C03C	17/245	X	
	AM	1-138145	5/31/89	Japan			X	
	AN	62-235223	10/15/87	Japan (abstract)	C03B	20/00		X
	AO	67/22389	11/1/67	Japan				X

EXAMINER: J. P. Ponce DATE CONSIDERED: 1/29/03
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FORM PTO-1449 (MODIFIED) LIST OF PATENTS AND PUBLICATIONS FOR APPLICANTS INFORMATION DISCLOSURE STATEMENT	ATTORNEY DOCKET NO. Berkey 48-8-2	SERIAL NO. To Be Assigned
	APPLICANT Berkey et al.	
	FILING DATE Herewith	GROUP: 903 U.S. Patent 09/876194 06/06/01

OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)

AA	Douglas Allan, Charlene Smith, N.F. Borrelli and T. P. Seward III, 193-nm excimer-laser-induced densification of fused silica, OPTICS LETTERS/Vol. 21, No. 24/December 15 1996, pp. 1960-1962
AB	Roger J. Araujo, Nicholas F. Borrelli and Charlene Smith, INDUCED ABSORPTION IN SILICA (A PRELIMINARY MODEL), SPIE Vol. 3424, 1998, pp. 25-32.
AC	George H. Beall, INDUSTRIAL APPLICATIONS OF SILICA, Reviews in Mineralogy, 29, pp. 469-505
AD	N.F. Borrelli, Charlene Smith, Douglas C. Allan and T.P. Seward III, Densification of fused silica under 193-nm excitation, J. Opt. Soc. Am B/Vol 14, No. 7/July 1997, pp. 1606-1615.
AE	J.W. Fleming and D.L. Wood, refractive index dispersion and related properties in fluorine doped silica, APPLIED OPTICS/Vol. 22, No. 19/October 1, 1983, pp.3102-3104.
AF	David L. Griscom, Optical Properties and Structure of Defects in Silica Glass, The Centennial Memorial Issue, 99[10], 1991, pp. 926-942.
AG	Hideo Hosono, Masafumi Mizuguchi, and Hiroshi Kawazoe, Effects of fluorine dimer excimer laser radiation on the optical transmission and defect formation of various types of synthetic SiO ₂ glasses, APPLIED PHYSICS LETTERS, Vol. 74, No. 19, 10 May 1999, pp. 2755-2757.
AH	Toshio Ibuki et al., ABSORPTION SPECTRA OF SiCl ₄ , SiCl ₆ , SiF ₃ CH ₃ AND GeF ₄ IN THE VUV REGION, Chemical Physics Letters, Vol. 136, No. 5, 15 May 1987, pp. 447-450.
AI	W.D. Kingery, H.K. Brown, and D. R. Uhlmann, Introduction to Ceramics, Second Edition, John Wiley & Sons, 1976. pg. 654.
AJ	M. Kyoto, Y. Ohgura, S. Ishikawa, Y. Ishiguro, Research and Development Group, Sumitomo Electric Industries Ltd, 1993 Chapman and Hall, pp. 2738-2744.
AK	I. H. Malitson, Interspecimen Comparison of the Refractive Index of Fused Silica, Journal of the Optical Society of America, Vol. 55, No. 10, pp. 1205-1209.
AL	James A. McClay and Angela S.L. McIntyre, 157 nm optical lithography: The accomplishments and the challenges, Solid State Technology, June 1999, pp. 57-68.
AM	Taro Moritani et al., "Glass Engineering Handbook," April 20, 1964, Asakura Shoten, p. 611, Clause 2.1 Fabrication.

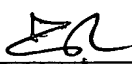

EXAMINER: *A. J. Dwyer*

DATE CONSIDERED: 1/29/03

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	APPLICANT Berkey et al.	
	FILING DATE Herewith	GROUP: 1756

OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)

	AN	M. Rothschild, D.J. Ehrlich & D.C. Shaver, <i>Effects Of Excimer Laser Irradiation On The Transmission, Index Of Refraction, And Density Of Ultraviolet Grade Fused Silica</i> , Appl. Phys. Lett 55(13) 9/25/99, pp. 1276-1278
	AO	Charlene M. Smith, Lisa A. Moore, <i>Fused Silica for 157 nm Transmittance</i> , SPIE Vol. 3676, 15-17 March 1999, pp. 834-841.
	AP	D.R. Sempolinski, T.P. Seward, C. Smith, N. Borrelli, C. Rosplock, <i>Effects of Glass Forming conditions on the KrF-Excimer-Laser-Induced Optical Damage In Synthetic Fused Silica</i> , Journal of Non-Crystalline Solids 203 (1996) pp. 69-77
	AQ	Richard H. Stulen & Donald W. Sweeney, <i>Extreme Ultraviolet Lithography</i> , Optics & Photonics News, August 1999, Vol. 10, No. 8, pp. 34-38
	AR	Richard E. Schenker & William G. Oldham, <i>Ultraviolet-induced Densification In Fused Silica</i> , J. Appl. Phys. 82 (3), 1 August 1997, pp. 1065-1071
	AS	Koji Tsukuma, N. Yamada, S. Kondo, K. Honda & H. Segawa, <i>Refractive Index, Dispersion and Absorption of Fluorine-Doped Silica glass in the Deep UV Region</i> , Journal of Non-Crystalline Solids 127 (1991), pp. 191-196
	AT	H. Takahashi, A. Oyobe, M. Kosuge & R. Setaka, <i>Characteristics of Fluorine-Doped Silica Glass</i> , Technical Digest: European Conference on Optical Communication, (1986) pp. 3-6
	AU	K. Tsukuma, N. Yamada, S. Kondo, K. Honda & H. Segawa, <i>Refractive Index, Dispersion and Absorption of Fluorine-Doped Silica Glass in the Deep UV Region</i> , Journal of Non-crystalline Solids 127 (1991), pp. 191-196
	AV	W. Vogel, <i>Chemistry of Glass</i> , The American Ceramic Society, Inc. (1985), pp. 203-205.
	AW	PTO: 96-0383, Journal, Title: Sheet Glass
	AX	Corning HPFS [®] , ArF Grade, Product Literature, 1999
	AY	Shin-Etsu Chemical Homepage, Semiconductor Materials Division, http://www.shinetsu.co.jp/english/profile/division/sem-div/sem-div.html , (5/17/99) pp. 1-2
	AZ	Purity and Chemical Reactivity, Isimoto Co., Ltd. Homepage, Purity and Chemical Reactivity, http://www.isimoto.com/isimoto/english/feature1.html , (5/17/99) pp. 1-3


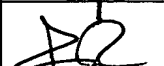
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	APPLICANT Berkey et al.	
	FILING DATE Herewith	GROUP: 1756

OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)

	AA1	Products for Optics, Isimoto Co., Ltd. Homepage, http://www.isimoto.com/isimoto/english/variation.3.html , (5/17/99) pp. 1-2
	AB1	Product Information, Isimoto Co., Ltd. Homepage, http://www.isimoto.com/isimoto/english/product_info.html , (5/17/99) pp. 1-4
	AC1	High Purity Quartz Glass Products, http://www.toshiba-ceramics.com/quartz.html , (5/17/99) pp. 1-2
	AD1	Heraeus Quarzglas, Fused Silica for 157 nm photomasks, Bruno Uebbing 157 nm workshop, 2/16/99 Phoenix/USA, pp. 1-5
	AE1	Heraeus, Product Literature, Quartz Glass for Optics Optical Properties, Edition 1994
	AF1	Heraeus Amersil, Product Literature, The Leader in Silica Glass & Fabricated Quartz Glass Semiconductor Products: CVD Tubes, (9/14/99)
	AG1	Heraeus Amersil, Product Literature, The Leader in Silica Glass & Fabricated Quartz Glass: Diffusion Tubes, (9/14/99)
	AH1	Heraeus Amersil, Product Literature, The Leader in Silica Glass & Fabricated Quartz Glass Semiconductor Products: Furnace Tubes, (9/14/99)
	AI1	Heraeus Amersil, Product Literature, The Leader in Silica Glass & Fabricated Quartz Glass Semiconductor Products: Windows, (9/14/99)
	AJ1	Heraeus Amersil, Product Literature, The Leader in Silica Glass & Fabricated Quartz Glass Semiconductor Products: Optical Properties, (9/14/99)
	AK1	Heraeus Amersil, Product Literature, The Leader in Silica Glass & Fabricated Quartz Glass Semiconductor Products: Thermal Properties, (9/14/99)
	AL1	Heraeus Amersil, Product Literature, The Leader in Silica Glass & Fabricated Quartz Glass Semiconductor Products: Raw Materials, (9/14/99)
	AM1	Heraeus Amersil, Product Literature, The Leader in Silica Glass & Fabricated Quartz Glass Semiconductor Products: Corporate Profile, (9/14/99)

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REFERENCE DESIGNATION				U.S. PATENT DOCUMENTS			
Examiner Initial		Document Number	Date	Name	Class	Sub-Class	Filing Date if Approp.
<i>AR</i>	AA	4,676,814	6/30/87	Ross et al.	65	3.12	
<i>AR</i>	AB	5,935,733	8/10/99	Scott et al.	430	5	
<i>AR</i>	AC	5,699,183	12/1997	Hiraiwa et al.	359	355	
	AD	6,087,283	7/2000	Jinbo et al.	501	54	
	AE						
	AF						
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	AJ						

FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Sub-Class	Translation	
							Yes	No
<i>AR</i>	AK	0 163 752	12/11/85	EPO	C03B	37/018	X	
	AL	0 691 312	1/10/96	EPO	C03C	3/06	X	
	AM	0 147 029	7/3/85	EPO	C03B	37/016	X	
	AN	0 691 312	1/10/96	EPO	C03C	3/06	X	
	AO	0 735 006	10/2/96	EPO	C03B	19/14	X	
	AP	257,590	3/24/27	United Kingdom				
<i>AR</i>	AQ	2,184,434	6/24/87	United Kingdom	C03B	20/00		

OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)			
<i>AR</i>	AR		Patent Abstracts of Japan, vol. 1996, no. 07, 31 July 1996, JP 08067530, SUMITOMO ELECTRIC IND LTD., 12 March 1996, Abstract.
<i>AR</i>	AS		Patent Abstracts of Japan, vol. 012, no 191 (C-501), 3 June 1988, JP 62-297233, FUJITSU LTD., 24 December 1987, Abstract.
<i>AR</i>	AT		Patent Abstracts of Japan, vol. 006, no. 252 (P-161), 10 December 1982, JP 57-147604, NIPPON DENKI KK, 11 September 1982, Abstract.

EXAMINER: <i>A. Tosasco</i>	DATE CONSIDERED: <i>11/29/03</i>
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1c903 U.S. PTO
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	FILING DATE Herewith	GROUP: 1756

REFERENCE DESIGNATION				U.S. PATENT DOCUMENTS			
Examiner Initial		Document Number	Date	Name	Class	Sub-Class	Filing Date if Approp.
JL	AA	1,283,333	10/29/18	Shaw			
	AB	2,188,121	1/23/40	Smith	47	78.1	
	AC	3,740,207	6/19/73	Bogrets et al.	65	67	
	AD	3,933,454	1/20/76	DeLuca	65	3	
	AE	4,221,825	9/9/80	Guerder et al.	427	34	
	AF	4,345,928	8/24/82	Kawachi et al.	65	18.2	
	AG	4,363,647	12/14/82	Bachman et al.	65	18.2	
	AH	4,612,023	9/16/86	Kreutzer et al.	65	32	
	AI	4,650,511	3/17/87	Koya et al.	65	30.1	
	AJ	4,666,495	5/19/87	Kreutzer et al.	65	258	
	AK	4,789,389	12/6/88	Schermerhorn et al.	65	31.2	
	AL	4,917,718	4/17/90	Berkey	65	108	
	AM	5,043,002	8/27/91	Dobbins et al.	65	31.2	
	AN	5,326,729	7/5/94	Yaba et al.	501	54	
	AO	5,364,433	11/15/94	Nishimura et al.	65	17.4	
	AP	5,410,428	4/25/95	Yamagata et al.	359	350	
	AQ	5,415,953	5/16/95	Alpay et al.	430	5	
	AR	5,474,589	12/12/95	Ohga et al.	65	397	
	AS	5,599,371	2/4/97	Cain et al.	65	413	
	AT	5,609,666	3/11/97	Heitmann	65	421	
	AU	5,655,046	8/5/97	Todoroki et al.	385	144	
	AV	5,683,483	11/4/97	Yosiaki et al.	65	102	
	AW	5,667,547	9/16/97	Christiansen et al.	65	17.4	
	AX	5,668,067	9/16/97	Araujo et al.	501	54	
	AY	5,679,125	10/21/97	Hiraiwa et al.	65	397	
JL	AZ	5,683,483	11/4/97	Yosiaki et al.	65	102	

EXAMINER: *J. Vasco* DATE CONSIDERED: *1/29/03*

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1c903 U.S. PTO
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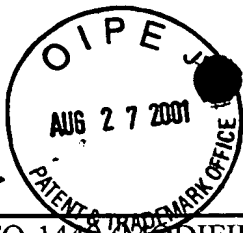
REFERENCE DESIGNATION				U.S. PATENT DOCUMENTS			
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FOREIGN PATENT DOCUMENTS								
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EC	AK	1 084 995A1	3/21/01	EPO	C03B	19/14	X	
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LIST OF PATENTS AND
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Berkey 48-8-2A

09/876,194

APPLICANT Berkey et al.

FILING DATE: June 6, 2001

GROUP: 2128

REFERENCE DESIGNATION

U.S. PATENT DOCUMENTS

Examiner Initial		Document Number	Date	Name	Class	Sub-Class	Filing Date if Approp.
	AA						
	AB						
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FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	Class	Sub-Class	Translation Yes	No
AL	AF	P2001-19450A	1/23/01	Japan	C03B	20/00	X	
AL	AG	1 084 995A1	3/21/00	EPO	C03B	19/14	X	
AL	AH	1 035 084	9/13/00	EPO	C03C	3/06	X	
AL	AI	WO 00/24685	5/4/00	PCT	C03C	3/06	X	

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